Hitachi S 9300 (200mm)

Hitachi S-9300 CD SEM Electron Optical System

* Wafer Size: 200mm
* Electron Gun: : Schottky emission source
* Accelerating voltage: 500V to 1600V, 10V steps
* Probe Current: 4~24pA with automated setting and measurement by Faraday cup.
* Electromagnetic Lens: 3-Stage Electromagnetic Lens system with boosting voltage.
* Objective Lens: 4 opening click stop
* Heated aperture is selectable/adjustable outside the vacuum
* Scan Coil: 2-Stage Electromagnetic Deflection.
* Astigmatism correction via 8-pole electromagnetic coil
* Magnification = 1000x to >300000x
* Field control method ; Continuously on for sample decharging at all voltages.
* Wafer imaging ability; Entire surface of 8” or 12” wafer
* Depth of focus: ≥ 1.0um at 80000x magnification
* Resolution: 3nm (800V) Retarding/Boosting Mode
* Hitachi Probe Tip
* Optical Microscope System: Monochrome Image
* Using CCD camera
* 110x Magnification
* Wafer Imaging: X coverage from 5 – 295mm
* Y coverage from 5 – 195mm
* Notch down / *Field of view: 1.2mm
* Chemicals Used: Nitrogen, Oil free Air (OFA), PCW \ Glycol
* Workstation: Model: HP B180L (9GB)
* O/S: Unix version HP-UX 10.20 or newer
* Software Version: 14.71 or newer
* SECS/GEM Communication Interface
* Dual XY Hitachi Microscale
* DSP Image Processing
* BSE Mode
* Multipoint Measurement Function
* Edge Roughness Function
* Automated Image Archiving Function
* Other: 200mm Wafer Handling System
(2) Cassette holders with ergo flippers
* Convertible to 300mm with conversion kit BRK-287006300 (subject to availability)
* Vib iso and vert inlet/exhaust (sub& availability)
* Water Chiller Unit (subject to availability).